

Amendments to the Claims:

This listing of the claims will replace all prior versions and listings of claims in the application:

Listing of Claims:

1 (withdrawn): An integrated semiconductor device comprising a plurality of semiconductor elements formed in a semiconductor layer and each having a source of a first-conductivity-type semiconductor, a drain of the first-conductivity-type semiconductor and a body region of a second-conductivity-type semiconductor between said source and said drain,

at least a predetermined part of the drain of one semiconductor element and a predetermined part of the drain of another semiconductor element being different in impurity concentration.

2 (withdrawn): The integrated semiconductor device according to claim 1, wherein said one semiconductor element and said another semiconductor element are different in breakdown voltage.

3 (withdrawn): The integrated semiconductor device according to claim 1, wherein said one semiconductor element has a high breakdown-voltage performance, said another semiconductor element has a lower breakdown-voltage performance than that of said one semiconductor element, and said at least the predetermined part of the drain of said one semiconductor element has an impurity concentration lower than that of said predetermined part of the drain of said another semiconductor element.

4 (withdrawn): The integrated semiconductor device according to claim 1, wherein said another semiconductor element has a breakdown voltage of at most 100 V.

5 (withdrawn): The integrated semiconductor device according to claim 1, wherein said source is located in a surface layer of said semiconductor layer and said body region encloses said source from the inside of said semiconductor layer.

6 (withdrawn): The integrated semiconductor device according to claim 1, wherein the drain of said one semiconductor element and the drain of said another semiconductor element are each constituted of a drain convergence region including a contact portion located in a surface layer of said semiconductor layer and connected to an interconnection, and a drain drift region of the first-conductivity-type semiconductor having an impurity concentration of the first conductivity type lower than that of said drain convergence region and being formed of said semiconductor layer except for said source, said body region and said drain convergence region.

7 (withdrawn): The integrated semiconductor device according to claim 6, wherein at least one of the drain drift region of the drain of said one semiconductor element and the drain drift region of the drain of said another semiconductor element has, in a portion between said source and said drain convergence region, a drain drift layer containing impurities of the first conductivity type with an impurity concentration higher than that of the drain drift region of said at least one of said one semiconductor element and said another semiconductor element.

8 (withdrawn): The integrated semiconductor device according to claim 7, wherein said plurality of semiconductor elements are classified into a group of semiconductor elements having a breakdown voltage of at least 100 V and a group of semiconductor elements having a breakdown voltage less than 100 V, for said group of semiconductor elements having a breakdown voltage of at least 100 V, a product $N \cdot d$ is in a range from 0.8 to 1.2E12 cm⁻² where d indicates a thickness from the bottom

to the surface of the drain drift region and N indicates an impurity concentration of the first conductivity type of the drain drift region and,

for said group of semiconductor elements having a breakdown voltage of less than 100 V, a product $N \cdot d$ is greater than $0.8E12 \text{ cm}^{-2}$ where d indicates a thickness from the bottom to the surface of the drain drift region and N indicates an impurity concentration of the first conductivity type of the drain drift region.

9 (withdrawn): The integrated semiconductor device according to claim 8, wherein said product $N \cdot d$ of the drain drift region of a semiconductor element in said group of semiconductor elements having a breakdown voltage of less than 100 V is greater than $1.2E12 \text{ cm}^{-2}$.

10 (withdrawn): The integrated semiconductor device according to claim 7, wherein for all of said plurality of semiconductor elements, a product $N \cdot d$ is at least $0.8E12 \text{ cm}^{-2}$ where d indicates a thickness from the bottom to the surface of the drain drift region and N indicates an impurity concentration of the first conductivity type of the drain drift region, regardless of the breakdown voltage.

11 (withdrawn): The integrated semiconductor device according to claim 1, wherein in both of said at least the predetermined part of the drain of said one semiconductor element and said predetermined part of the drain of said another semiconductor element, an impurity concentration is high at a location in a surface layer of said semiconductor layer and the impurity concentration decreases as the location approaches the inside.

12 (withdrawn): The integrated semiconductor device according to claim 1, wherein said semiconductor elements are any of a MOSFET (Metal Oxide Semiconductor Field-Effect Transistor), an IGBT (Insulated Gate Bipolar Transistor), a bipolar transistor and a diode.

13 (currently amended): A method of manufacturing an integrated semiconductor device having a plurality of semiconductor elements formed in a well region of a semiconductor layer and each having a source of a first-conductivity-type semiconductor, a drain of the first-conductivity-type semiconductor and a body region of a second-conductivity-type semiconductor between said source and said drain, and a drift layer of the first-conductivity-type in an upper region of said well region, comprising the steps of:

implanting impurities concurrently into ~~at least a predetermined part of the drain a first drift layer~~ of one semiconductor element and into ~~a predetermined part of the drain a second drift layer~~ of another semiconductor element, an implantation mask being used that includes a portion corresponding to ~~the drain said first drift layer~~ of said one semiconductor element and having a first opening ratio as well as a portion corresponding to ~~the drain said second drift layer~~ of said another semiconductor element and having a second opening ratio different from said first opening ratio, wherein

 said one semiconductor element has a breakdown voltage higher than that of said another semiconductor element,

- said implantation mask being used has said first opening ratio smaller than said second opening ratio, and

 said one semiconductor element is adjacent to said another semiconductor element; and
 providing, in said semiconductor layer, a wall-shaped element-isolation insulating film for isolating said one semiconductor element from said another semiconductor element, prior to said step of implanting impurities; and

 annealing said integrated semiconductor device after said step of implanting impurities to diffuse said impurities.

14 (canceled)

15 (canceled)

16 (original): The method of manufacturing an integrated semiconductor device according to claim 13, wherein

 said implantation mask has masking portions and openings in the shape of stripes, and said implantation mask is used by being placed with said stripes arranged in the direction parallel to a carrier path from the source to the drain of said semiconductor elements.

17 (original): The method of manufacturing an integrated semiconductor device according to claim 13, wherein

 said implantation mask being used is a mesh implantation mask having dot-like openings dispersed in a masking portion.

18 (original): The method of manufacturing an integrated semiconductor device according to claim 13, wherein

 said implantation mask being used is a dot implantation mask having dot-like masking portions dispersed in an opening.

19 (new): The method of manufacturing an integrated semiconductor device according to claim 13, wherein

 an impurity concentration of said drift layer is higher than said well region.

20 (new): The method of manufacturing an integrated semiconductor device according to claim 13, wherein

 an impurity concentration of said first drift layer is lower than said second drift layer.